

Implications of laser-doping parameters and contact opening size on contact resistivity

Jonas D. Huyeng^{1,2,*}, Marco Ernst¹, Kean Chern Fong¹, Daniel Walter¹, and Andrew Blakers¹

¹Centre of Sustainable Energy Systems, Australian National University, Canberra, ACT 2600, Australia (*marco.ernst@anu.edu.au)

²Fraunhofer Institute for Solar Energy Systems (ISE), Heidenhofstrasse 2, 79110 Freiburg, Germany

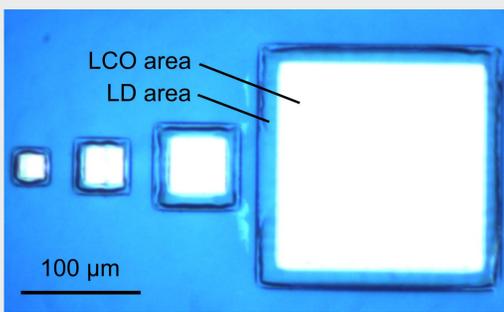
Derivation of an ohmic local contact analysis (OLCA) to determine the contact resistivity of localized contacts with simple sample structure

Motivation

- **Localized contacts**
 - Important for **advanced cell structures**
 - Cannot be measured by transfer length method (**TLM**)
 - Alternative method to determine contact resistivity ρ_c : **OLCA**

Sample fabrication

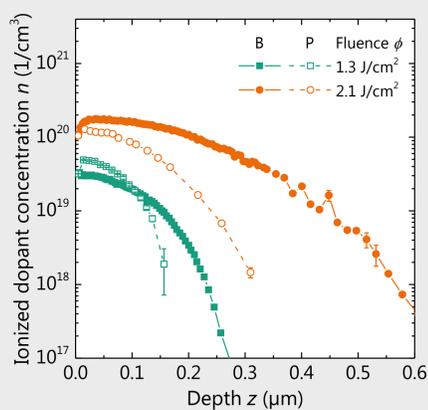
- **Localized contacts** with laser processing (Excimer laser)
 - Laser doping (**LD**): varying **fluence** and **size**
 - Laser contact opening (**LCO**): adjusting size
 - Boron (**B**) and Phosphorus (**P**) dopant sources



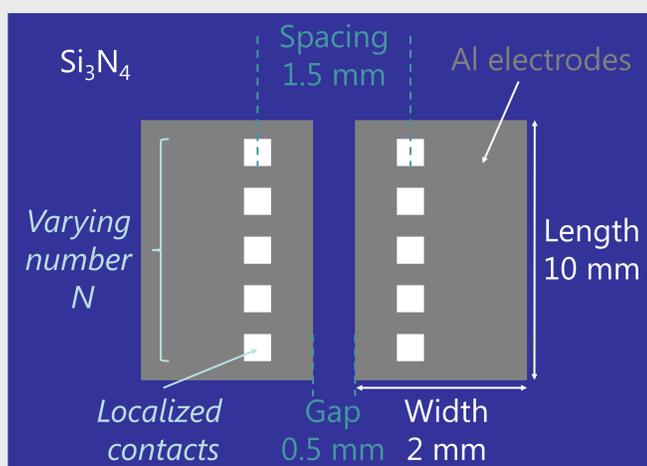
Microscope image illustrating the variation of laser-doping size (variable aperture) after laser-contact opening confined to a region smaller than the laser-doped areas.

- **Ohmic** sample structure: **Localized contact** polarity = **base** polarity

- Large-area laser doping (stitched spots) to measure
 - **Sheet resistivity** R_{\square} (4PP)
 - **Dopant profile** $n(z)$ (ECV)



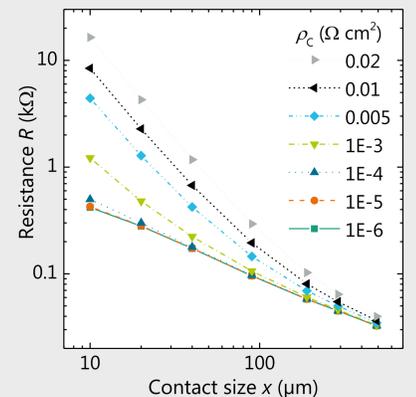
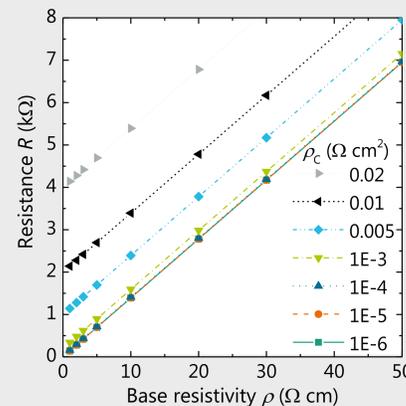
- **LPCVD** Si₃N₄ for surface passivation
- **PVD** aluminium for **electrode** metallization



Sketch of the sample structure: Localized contacts are placed collinearly and equidistant under electrodes with defined spacing.

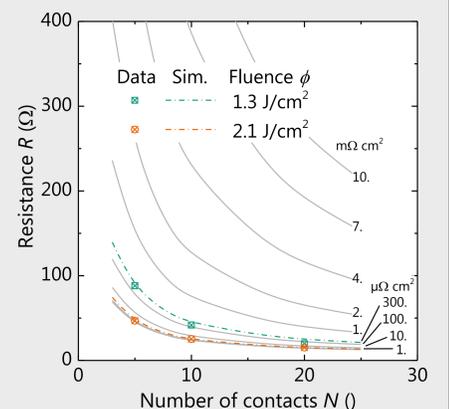
Numerical simulation

- **Quokka 3** simulation of ohmic structures
- Parameter sweeps to determine **critical parameters** ρ_c, x

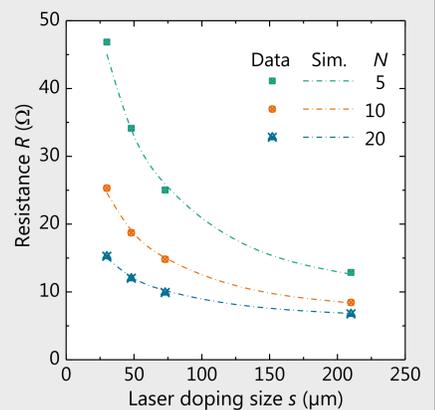


Contact resistivity

- Initial set of **simulations**
- Compare $R(N)$ **measurements** and simulation results
- Perform additional **simulations** in relevant range



- **Consistency** check
 - Determine ρ_c only for spot size $s = 30$ μm
 - Simulate **all** other spot sizes
 - Plot measurement (**data**) and simulation (**no fit**)



After forming gas anneal, 300 °C:

Fluence ϕ (J/cm ²)	Boron		Phosphorus	
	R_{\square} (Ω/□)	ρ_c (mΩ cm ²)	R_{\square} (Ω/□)	ρ_c (mΩ cm ²)
1.3	97 ± 9	0.42	186 ± 20	0.35
2.1	36 ± 4	0.04	60 ± 7	0.07

Conclusion

- **OLCA** method was **successfully** applied
- **Localized contacts** with **PVD Al** show **low** $\rho_c < 0.1$ mΩ cm²
 - Comparable to similar large area dopings (TLM)
- **Method** can be applied to **other fabrication methods**, such as screen-printed metallization

